ARTICLE TYPE

Supplementary Information - Influencing FTO thin film growth with thin seeding layers: A route to microstructural modification [†]

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Fig. S1 SEM and AFM images illustrating the morphology and surface roughness features of FTO thin films formed at various AACVD deposition times; A) 10 sec, B) 30 sec, C) 60 sec, D) 600 sec.



Fig. S2 SEM and AFM images illustrating the morphology and surface roughness features of FTO thin films formed at various APCVD deposition times; A) 10 sec, B) 20 sec, C) 30 sec, D) 40 sec, E) 50 sec, F) 60 sec, G) 120 sec.



Fig. S3 UV-Vis.-Near IR Reflectance spectra of FTO thin films formed at various APCVD deposition times or AACVD seed - APCVD overlay times.



Fig. S4 Estimated TAUC method calculated direct optical bandgap spectra of FTO thin films formed at various APCVD deposition times or AACVD seed - APCVD overlay times.



Fig. S5 Illustrative Raman spectra of FTO thin films formed at various AACVD seed - APCVD overlay deposition times.